

Abstract

The invention provides an indium oxide-tin oxide powder which can be produced at low cost and which can provide a high-density sputtering target having a prolonged target life, and a sputtering target employing the powder.

The indium oxide-tin oxide powder containing an In-Sn oxide as a predominant component is characterized in that the oxide powder contains no compound oxide ($\text{In}_4\text{Sn}_3\text{O}_{12}$) detectable through X-ray diffraction and has a SnO_2 solid solution amount in In_2O_3 of 2.3 mass% or more, the SnO_2 solid solution amount being calculated from the precipitated SnO_2 content (mass%) obtained from the ratio between integral diffraction intensity attributed to In_2O_3 (222) and integral diffraction intensity attributed to SnO_2 (110).